PROCEEDINGS OF SPIE

Advanced Fabrication Technologies for Micro/Nano Optics and Photonics XI

Georg von Freymann Winston V. Schoenfeld Raymond C. Rumpf Editors

28–31 January 2018 San Francisco, California, United States

Sponsored by SPIE

Cosponsored by Nanoscribe GmbH (Germany)

Published by SPIE

Volume 10544

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Author(s), "Title of Paper," in Advanced Fabrication Technologies for Micro/Nano Optics and Photonics XI, edited by Georg von Freymann, Winston V. Schoenfeld, Raymond C. Rumpf, Proceedings of SPIE Vol. 10544 (SPIE, Bellingham, WA, 2018) Seven-digit Article CID Number.

ISSN: 0277-786X

ISSN: 1996-756X (electronic)

ISBN: 9781510615731

ISBN: 9781510615748 (electronic)

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

SPIE.org

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Printed in the United States of America Vm7 i ffUb 5 app WJUhY az a Wzi bXYf Wz bdY Zfca GD-9.

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